

Advanced Magnetics For 125-mm ID targets

The most versatile rotary magnet system available, Sputtering Components Advanced Magnetics for 125-mm ID targets are designed to provide high quality, uniform coatings for your application.

- Designed using 3D finite element analysis software - for meeting your application requirements
- Carefully matched, high-strength magnets that are factory calibrated using an automated magnet bar measurement tool - for uniform coatings
- Fully encapsulated magnets and robust construction - for many years of trouble-free operation
- Long-life, multi-roller system - for reliable sputter up, sputter down or off-angle sputtering
- Magnetic positioning points that are easily set using simple tools - for easy uniformity adjustment
- A simple installation procedure with solutions for vertical installation and connecting to end blocks from other manufacturers

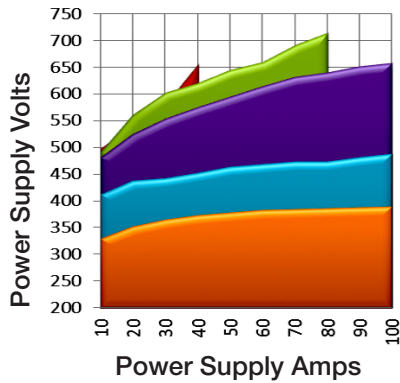


TECHNICAL SPECIFICATIONS

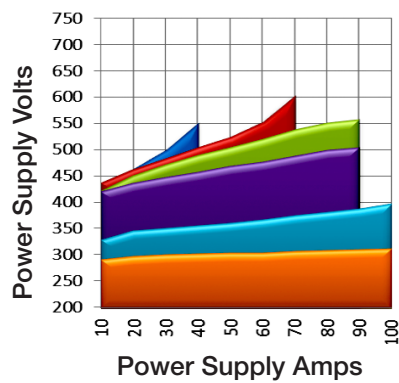
| | | Maximum Target Diameter | Gauss (Typical) | Sputter Angle | Patented Turnaround* | Application |
|-----------|---|-------------------------|-----------------|---------------|----------------------|--|
| TRM-Bar™ | ▶ | 160 mm | 540 | ± 12° | No | Standard targets, most materials |
| mQRM-Bar™ | ▶ | 170 mm | 620 | ± 15° | Yes | Thicker targets, high material utilization |
| QRM-Bar™ | ▶ | 180 mm | 870 | ± 21° | Yes | Thickest targets, ITO, electrical grade film |

*Improves target utilization

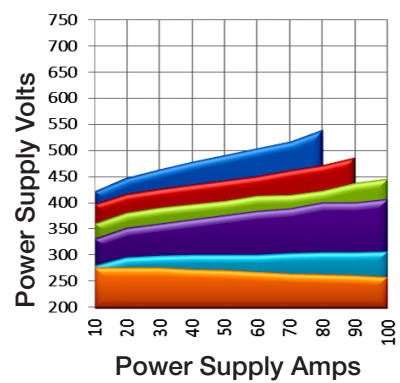
TRM-Bar™



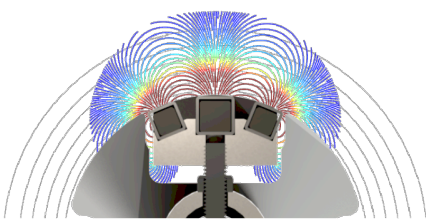
mQRM-Bar™



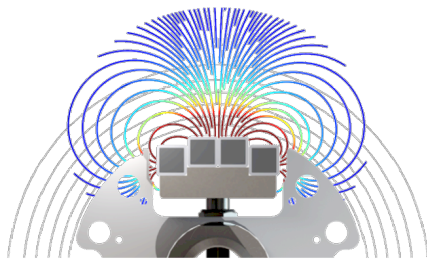
QRM-Bar™



ODs, from bottom to top: 135 mm 145 mm 155 mm 160 mm 165 mm 175 mm



- Small magnet, three-row design
- Narrowest deposition profile minimizes coating loss to shields
- Multiple turn-around design options specific to your application
- Easy change turn-arounds



- Small magnet, four-row design
- Patented staggered turn-around design for better target utilization
- Improved performance and reduced impedance
- Stable plasma impedance over the target life



- Large magnet, four-row design
- Patented staggered turn-around design for better target utilization
- Improved performance
- Best plasma impedance stability over the target life